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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/832,093	04/11/2001	Shigeo Ishikawa	Q64059	8684
7.	590 05/23/2002			<u> </u>
SUGHRUE, MION, ZINN, MACPEAK & SEAS 2100 Pennsylvania Avenue, N.W. Washington, DC 20037			EXAMINER	
			BRAIRTON, SCOTT A	
			ART UNIT	PAPER NUMBER
		2823	•	
			DATE MAILED: 05/23/2002	

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)			
Office Action Summary	09/832,093	ISHIKAWA, SHIGEO			
. Office Action Summary	Examiner	Art Unit			
The MAILING DATE of this communication and	Scott A Brairton	2823			
The MAILING DATE f this communication appears on the cover sheet with the cerrespondence address Period for Reply					
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). - Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b). Status					
1)⊠ Responsive to communication(s) filed on 11 A	April 2001 .				
2a) ☐ This action is FINAL . 2b) ☑ Thi	s action is non-final.				
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims					
4)⊠ Claim(s) <u>1-14</u> is/are pending in the application.					
4a) Of the above claim(s) is/are withdrawn from consideration.					
5) Claim(s) is/are allowed.					
6)⊠ Claim(s) <u>1-14</u> is/are rejected.					
7)⊠ Claim(s) is/are objected to.					
8) Claim(s) are subject to restriction and/or election requirement. Application Papers					
9)☐ The specification is objected to by the Examiner.					
10) ☐ The drawing(s) filed on is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.					
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).					
11) The proposed drawing correction filed on is: a) approved b) disapproved by the Examiner.					
If approved, corrected drawings are required in reply to this Office action.					
12)☐ The oath or declaration is objected to by the Examiner.					
Priority under 35 U.S.C. §§ 119 and 120					
13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).					
a)⊠ All b)□ Some * c)□ None of:					
1. Certified copies of the priority documents have been received.					
2. Certified copies of the priority documents have been received in Application No					
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 					
14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).					
 a) ☐ The translation of the foreign language provisional application has been received. 15)☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121. 					
Attachment(s)					
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449) Paper No(s) 4.		(PTO-413) Paper No(s) atent Application (PTO-152)			
J.S. Patent and Trademark Office					

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DETAILED ACTION

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-14 are rejected under 35 U.S.C. 103(a) as being unpatentable over Okamoto et al (U.S. Patent No. 6,265,288) in combination with Li et al (U.S. Patent No. 5,772,771).

Okamoto et al discloses in figures 1-4 and related text a method of forming a film comprising the steps of starting a supply of reaction gas comprising one of SiH₄, SiF₄ or TEOS at a first flow rate (col. 5, lines 19-29) into a chamber in which plasma is formed, such that an initial film is formed on a wafer and starting supply of the reaction gas at a second flow rate (col. 6, lines 16-29) into the chamber which the plasma is formed after starting the supply of reaction gas at a first flow rate, such that the film is formed on the initial film, the first flow rate being smaller than the second flow rate (col. 6, lines 16-18).

Okamoto fails to disclose a chamber wherein a first nozzle is provided on the chamber above a center region of the wafer and wherein second nozzles are provided on the sidewalls of the chamber above the same wafer.

Li et al teaches in figures 1-5 and related text a chamber wherein a first nozzle (figure 1, 56) is provided on the chamber above a center region of the wafer (figure 1, 20) and wherein second nozzles (figure 1, 34) are provided on the sidewalls of the chamber above the same wafer.

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It would have been obvious to one of ordinary skill at the time of the invention to combine the teachings of Li with the method of Okamoto in order to improve deposition thickness uniformity.

The selection of the selection of the flow rates, film thickness and time intervals is obvious because it is a matter of determining optimum process conditions by routine experimentation with a limited number of species. In re Jones, 162 USPQ 224 (CCPA 1955)(the selection of optimum ranges within prior art general conditions is obvious) and In re Boesch, 205 USPQ 215 (CCPA 1980)(discovery of optimum value of result effective variable in a known process is obvious).

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Scott A Brairton whose telephone number is (703) 605-4213. The examiner can normally be reached on M-F, 8:30AM-5:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael Fahmy can be reached on (703) 308-4918. The fax phone numbers for the organization where this application or proceeding is assigned are (703) 746-4082 for regular communications and (703) 746-4082 for After Final communications.

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Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

Scott A Brairton Examiner Art Unit 2823

sab May 20, 2002

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